

Notice of References Cited	Application/Control No. 10/691,299	Applicant(s)/Patent Under Reexamination AGNELLO ET AL.	
	Examiner Mursalin B. Hafiz	Art Unit 2814	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-6,150,249	11-2000	Lee et al.	438/592
	B	US-2002/0151170 A1	10-2002	Maex et al.	438/638
	C	US-5,989,988	11-1999	linuma et al.	438/592
	D	US-5,356,837	10-1994	Geiss et al.	438/535
	E	US-6,743,721 B2	06-2004	Lur et al.	438/683
	F	US-6,281,102 B1	08-2001	Cao et al.	438/592
	G	US-5,780,361	07-1998	Inoue, Ken	438/683
	H	US-6,495,460	12-2002	Bertrand et al.	438/683
	I	US-6,873,051 B1	03-2005	Paton et al.	257/751
	J	US-6,432,805 B1	08-2002	Paton et al.	438/592
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Mo, Hong-Siang; Qu, Xin-Ping; Liu, Jian-Hai; Ru, Guo-Ping; Li, Bing-Zong; "Formation and properties of ternary silicide (CoxNi1-x)si2 thin films", Oct. 22-23, 1998, IEEE, 271-274
	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.